

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1. (Currently Amended) An exposure apparatus comprising:  
an optical system for guiding light from a light source to a reflection reticle ~~an object~~;  
a reticle chuck ~~holding member~~ for holding the reflection reticle by electrostatic suction  
~~object~~; and  
a reference surface providing in the reticle chuck,  
~~a measuring device for measuring position of the holding member by using a reference~~  
~~surface provided in the holding member~~, wherein the reference surface is located in an area  
corresponding to a reticle pattern of the reflection reticle ~~object~~ which is held by the reticle  
chuck, ~~holding member~~  
wherein the reference surface is located substantially at a position corresponding to the  
center of the reflection reticle which is held by the holding reticle chuck.

2. (Canceled)

3. (Currently Amended) ~~An~~ The exposure apparatus according to claim 1, wherein the  
position substantially corresponding to the center of the reflection reticle ~~object~~ is fixed to a  
position substantially corresponding to the center of the reticle chuck ~~holding member~~.

4-6. (Canceled)

7. (Currently Amended) ~~An~~ The exposure apparatus according to claim 1, exposes an the object by scanning the reflection reticle object.

8. (Currently Amended) ~~An~~ The exposure apparatus according to claim 1, wherein the light source is an EUV light source.

9. (Currently Amended) An exposure method comprising the steps of:  
measuring position of a reflection reticle ~~an object~~ founding on a reference surface being provided in a reticle chuck ~~holding member~~ which holds the relection reticle by electrostatic suction ~~object~~, the reference surface being located substantially at a position corresponding to the center of the reflection reticle which is held by the holding reticle chuck ~~in an area corresponding to the object~~,

adjusting the position of the object in accordance with the measurement results; and  
exposing the object by guiding light from a light source to the object.

10. (Currently Amended) A device fabrication method comprising the steps of:  
exposing an object by an exposure apparatus according to claim 1 ~~which comprises an optical system for guiding light from a light source to an object, a holding member for holding the object, and a measuring device for measuring position of the holding member by using a reference surface provided in the holding member, wherein the reference surface is located in an area corresponding to the object which is held by the holding member~~; and  
developing the object that has been exposed.